

10688072\_CLS  
Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10688072 on June 16, 2004

Original Classifications

5	250/396R
4	250/492.21
3	250/287
3	250/288
3	250/309
3	250/423R
3	250/427
2	250/398
2	250/492.2
2	315/111.81

Cross-Reference Classifications

9	250/423R
6	250/492.2
4	250/287
4	250/397
4	250/398
3	313/359.1
3	313/363.1
3	315/111.41
3	315/111.81
2	250/281
2	250/288
2	250/307
2	250/310
2	250/396R
2	250/427
2	313/231.31
2	313/362.1
2	315/111.31
2	445/50

Combined Classifications

12	250/423R
8	250/492.2
7	250/287
7	250/396R
6	250/398
5	250/288
5	250/397
5	250/427
5	315/111.81
4	250/492.21

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4 313/359.1  
3 250/281  
3 250/309  
3 313/362.1  
3 313/363.1  
3 315/111.41  
2 216/41  
2 250/282  
2 250/307  
2 250/310  
2 250/492.3  
2 313/231.31  
2 315/111.31  
2 347/123  
2 445/50

10688072\_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10688072 on June 16, 2004

12	250/423R	(3 OR, 9 XR)
	Class 250 :	RADIANT ENERGY
	250/423R	ION GENERATION
8	250/492.2	(2 OR, 6 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
7	250/287	(3 OR, 4 XR)
	Class 250 :	RADIANT ENERGY
	250/281	IONIC SEPARATION OR ANALYSIS
	250/286	.Ion beam pulsing means with detector synchronizing means
	250/287	..With time-of-flight indicator
7	250/396R	(5 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/396R	WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
6	250/398	(2 OR, 4 XR)
	Class 250 :	RADIANT ENERGY
	250/396R	WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
	250/398	.With target means
5	250/288	(3 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/281	IONIC SEPARATION OR ANALYSIS
	250/288	.With sample supply means
5	250/397	(1 OR, 4 XR)
	Class 250 :	RADIANT ENERGY
	250/396R	WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
	250/397	.With detector
5	250/427	(3 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/423R	ION GENERATION
	250/427	.Electron bombardment type

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- 5 315/111.81 (2 OR, 3 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS  
  
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE  
315/111.81 .Electron or ion source
- 4 250/492.21 (4 OR, 0 XR)  
Class 250 : RADIANT ENERGY  
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
250/492.2 .Irradiation of semiconductor devices  
250/492.21 ..Ion bombardment
- 4 313/359.1 (1 OR, 3 XR)  
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
- 3 250/281 (1 OR, 2 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS
- 3 250/309 (3 OR, 0 XR)  
Class 250 : RADIANT ENERGY  
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED  
PARTICLES  
250/309 .Positive ion probe or microscope type
- 3 313/362.1 (1 OR, 2 XR)  
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION  
313/362.1 .Supplying ionizable material (e.g., gas or  
vapor)
- 3 313/363.1 (0 OR, 3 XR)  
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION  
313/363.1 .Extraction or target electrode
- 3 315/111.41 (0 OR, 3 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS  
  
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE  
315/111.21 .Plasma generating  
315/111.41 ..With magnetic field
- 2 216/41 (1 OR, 1 XR)  
Class 216 : ETCHING A SUBSTRATE: PROCESSES

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MASKING OF A SUBSTRATE USING MATERIAL RESISTAN  
TO AN ETCHANT (I.E., ETCH RESIST)

2 250/282 (1 OR, 1 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS  
250/282 .Methods

2 250/307 (0 OR, 2 XR)  
Class 250 : RADIANT ENERGY  
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED  
PARTICLES  
250/307 .Methods

2 250/310 (0 OR, 2 XR)  
Class 250 : RADIANT ENERGY  
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED  
PARTICLES  
250/310 .Electron probe type

2 250/492.3 (1 OR, 1 XR)  
Class 250 : RADIANT ENERGY  
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
250/492.3 .Ion or electron beam irradiation

2 313/231.31 (0 OR, 2 XR)  
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES  
313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS  
313/231.31 .Plasma

2 315/111.31 (0 OR, 2 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS  
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE  
315/111.21 .Plasma generating  
315/111.31 ..With extraction electrode

2 347/123 (1 OR, 1 XR)  
Class 347 : INCREMENTAL PRINTING OF SYMBOLIC INFORMATION  
347/111 ELECTRIC MARKING APPARATUS OR PROCESSES  
347/112 .Electrostatic  
347/120 ..By information carrying flow of invisible  
charged particles  
347/123 ...Specific ionographic head

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2 445/50 (0 OR, 2 XR)  
Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR  
DEVICE MANUFACTURING  
445/1 PROCESS  
445/46 .Electrode making  
445/49 ..Electrode shaping  
445/50 ...Emissive type